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1. A plasma treatment apparatus comprising:
an airtight treatment chamber;
a lower electrode including a mount portion on
5 which an object is to be mounted, the lower electrode
being movable up and down in the treatment chamber;
a power supply system to supply high-frequency
power to the lower electrode;
an elevator mechanism to move the lower electrode
10 up and down;
a conductive wall body substantially surrounding
the elevator mechanism in close proximity and forming a
path reaching to a floor portion of the treatment
chamber; and
15 a conductive member provided around the lower
electrode and electrically connecting an inner wall of
the treatment chamber and the wall body.
2. A plasma treatment apparatus according to
claim 1, wherein a through hole or a groove to let
20 escape air remaining in a space between the elevator
mechanism and the wall body is formed in the wall body.
3. A plasma treatment apparatus according to
claim 1, wherein an opening portion through which the
object is carried in and out is formed in the wall
25 body.
4. A plasma treatment apparatus according to
claim 3, wherein the elevator mechanism moves down the

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lower electrode to a position opposing to the opening portion.

5 5. A plasma treatment apparatus according to claim 3, wherein a cover to cover a driving portion of the elevator mechanism is formed in the elevator mechanism.

10 6. A plasma treatment apparatus according to claim 5, wherein the cover is disposed at least between the driving portion and the opening where the object passes.

15 7. A plasma treatment apparatus according to claim 1, wherein the conductive member partitions the treatment chamber into an exhaust space to which an exhaust system is connected and a discharge space in which plasma is generated.

20 8. A plasma treatment apparatus according to claim 7, wherein the conductive member has a plurality of through holes and functions as a baffle plate which communicates the discharge space and the exhaust space through the through holes.

9. A plasma treatment apparatus according to claim 1, wherein the high-frequency power supplied from the power supply system has a frequency of at least 10 MHz.

25 10. A plasma treatment apparatus according to claim 1, wherein the treatment chamber is grounded.

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